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| Total number of printed pages – 3 | | | | | | | | | B. | Tech |
| Registration No.: | | | | | | | | | | |

Seventh Semester (Special) Examination – 2013

VLSI DESIGN

BRANCH: CSE, EEE, ELECTRICAL, IT

QUESTION CODE: D 458

Full Marks - 70

Time: 3 Hours

Answer Question No. 1 which is compulsory and any five from the rest.

The figures in the right-hand margin indicate marks.

- Answer the following questions:
 - (a) Define the terms Regularity, Modularity and Locality.
 - (b) Why is Silicon preferred over other semiconductor materials in the IC Industry?
 - (c) What is the difference between full custom and FPGA design styles?
 - (d) Draw the stick diagram and the layout diagram of a 2-input MAYD gate.
 - (e) Calculate the oxide capacitance for a MOS capacitor for the oxide thickness, $t_{ox} = 100 \text{Å}$. Assume $\epsilon_{ox} = 3.97 \epsilon_{o}$
 - (f) Draw the CMOS implementation of a NOT gate. What is the minimum power supply voltage required for a CMOS inverter so that it can operate properly.
 - (g) Implement a 2 input XOR gate using transmission gates.
 - (h) If a domino gate input is initially a '1' at the start of evaluation, can it make any other transition during evaluation? Why or Why not?
 - (i) Implement an edge triggered DFF using CMOS.
 - (j) What is CPL logic? Give one advantage of this style of implementation.

- 2. (a) Calculate the threshold voltage of a NMOS transistor with substrate grounded and the following parameters-Substrate and the polysilicon gate doping are respectively given as N_{A(substrate)} = 1.5 × 10¹⁵/cm³, N_{D(PolySi gate)} = 1×10²⁰/cm³. The oxide thickness is t_{ox}=1000Å and the fixed oxide charge, Q_{OX}= q.1×10¹⁰C/cm². Assume no threshold adjust implantation impurities are added.
 - (b) Draw and explain the Y-Chart for VLSI Design Flow. 5
- 3. (a) For the nMOS enhancement mode transistor, calculate the drain current for $\lambda = 0.05 V^{-1}$ and $\left(\frac{W}{L}\right) = 2$. Given that $K_n' = \mu_n C_{ox} = 20 \ \mu A/V^2$,

$$\left(\frac{L}{L_{eff}}\right) = \frac{1}{2}$$
, VG = 3V, VS = 1V, VD = 5 V, VT0 = 1 V. What does this result indicate 2 CENTRAL (See Section 2)

- indicate 2 CENTRAL

 (b) Derive the current equation using the gradual channel approximation theory for a n-channel MOS transistor operating in the linear region. 5
- Design a transister level CMOS logic circuit to implement a 2×1 MUX using the following styles: Static CMOS, Dynamic CMOS, Pseudo NMOS and Domino Logic.
- (a) With the help necessary band diagram show the electrical behaviour of a MOS system at "surface inversion". Derive the maximum depletion depth during this condition.
 - (b) Explain the VTC of a CMOS Inverter with proper labeling. Also derive the $V_{\rm OH}$ and $V_{\rm oL}$ of a CMOS Inverter.
- 6. (a) Define the terms rise time and fall time with suitable diagrams. How does the C_{load} effect propagation delay of a circuit?
 - (b) What are the precharge and evaluate phase of a dynamic logic? Name two techniques to avoid the problem of charge sharing in dynamic circuits. Give suitable diagrams to aid yours answer.

- Design a circuit described by the function $Y = \overline{A \cdot (B + C) \cdot (D + E)}$ using CMOS logic. Also find the equivalent CMOS inverter circuit for simultaneous switching of all inputs assuming that $\left(\frac{W}{L}\right)_{n} = 5$ for all **pMOS** transistors and $\left(\frac{W}{L}\right) = 2$ for all *n*MOS transistors.
 - Calculate the switching threshold voltage V_{th} of the two-input CMOS NOR (b) gate with the following parameters: $(W/L)_p = 4$, $(W/L)_n = 1$, $V_{Ton} = 0.7V$, $V_{Top} = -0.7V$, $\mu_n C_{ox} = 40 \mu A/V^2$, $\mu_p C_{ox} = 20 \mu A/V^2$, $V_{DD} = 5V$. Compare the result with the switching threshold voltage V_{th} of a CMOS inverter with the same parameters. 5
- Write short notes on any two of the following: 8.

5×2

- PMOS Fabrication Steps (a)
- MOSFET Capacitance (b)
- Small Geometry effects (c)
- 1T DRAM Cell (d)
- BIST. (e)